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AL.	AA	4,890,294	12/26/89	Nishimae et al.	372	57	<u> </u>	
M	AB	5,009,963	04/23/91	Ohmi et al.	428	472.2		
10	AC	5,897,847	04/27/99	Jursich et al.	423	219		
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Sheet 1 of 8 Serial No. U.S. Department of Commerce, Patent and Trademark Office Atty Docket No. M-7697 US INFORMATION DISCLOSURE STATEMENT BY APPLICANT Applicant(s) (Use several sheets if necessary) Tom A. Watson et al. Filing Date Group 9 & 28 2003 Unknown U.S. Patent Documents \*Examiner Document Filing Date Initial Number Date Name Class Subclass If Appropriate 5,047,115 09/10/1991 Charlet et al. 643 AA 156 AB 5,444,259 08/22/1995 452.21 Ohmi 250 Ohmi et al. AC 5,360,768 11/01/1994 437 238 AD AE AF AG AH ΑI AJ AK Foreign Patent Documents Translation Document Class Yes No Date Country Subclass AL EP 0794 598 A1 10/09/1997 Europe AM AN AO AP OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.) AQ Ultra Clean Manufacturing Technology Co., Ltd., "CRP & FP - Gas Supply System for the Next Generation of ULSI," (Undated) 16 pages AR N. Miki et al., "Vapor-Liquid Equilibrium of the Binary System HF-H20 Extending to Extremely Anhydrous Hydrogen Fluoride," (March 1990) J. Electrochem. Soc., Vol. 137, No. 3, ©The Electrochemical Society, Inc., pages 787 - 790 N. Maeno, et al., "Fluorine Passivation of Metal Alloy Surface With Volatile Reaction Enhanced AS mechanism," (July 1992) J. Electrochem. Soc., Vol. 139, No. 7, pages 1865 - 1869 Examiner nuez Date Considered

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.

Sheet 2 of 8 U.S. Department of Commerce, Patent and Trademark Office Atty Docket No. Serial N M-7697 US INFORMATION DISCLOSURE STATEMENT BY APPLICANT Applicant(s) (Use several sheets if necessary) Tom A. Watson et al. Group 282 Filing Date Unknown U.S. Patent Documents Document Filing Date \*Examiner Class Number Subclass If Appropriate Initial Date Name AA AB AC AD ΑE AF AG AH ΑI ΑJ ΑK Foreign Patent Documents **Translation** Class Subclass Yes No Document Date Country AL AM AN AO AP ART (Including Author, Title, Date, Pertinent Pages, Etc.) N. Maeno, et al., "Fluorine Passivation of Metal Alloy Surface With Volatile Reaction Enhanced AQ mechanism," (July 1992) J. Electrochem. Soc., Vol. 139, No. 7, pages 1865 - 1869 Phil Danielson, "Gas Loads From Elastomer Seals," (January 1999) Vacuum & Thinfilm, pages 14 - 15 AR STELLA CHEMIFA Corporation, "Fluorine Passivation Technology," (1998) 11 pages AS

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.

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AL	AR			inant Effects in Discharg pages 1974 – 1981	e-Excited KrF	Lasers," (April	1 20, 1992)				
AR	AS	W. Holber et al. pages 26 - 29	, "Reducing PFC	Emissions From CVD R	eactors," (Mai	rch 1999) Vacu	um & Thinfil	lm,			
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Sheet 5 of 8 U.S. Department of Commerce, Patent and Trademark Office Atty Docket No. ... . Serial No. M-7697 US INFORMATION DISCLOSURE STATEMENT BY APPLICANT Applicant(s) (Use several sheets if necessary) Tom A. Watson et al. Filing Date Group Unknown U.S. Patent Documents \*Examiner Document Filing Date Initial Number Date Class Subclass Name If Appropriate AA AB AC AD AE AF AG AH AI AJ AK Foreign Patent Documents Translation Document Class Subclass Date Country Yes No AL AM AN AO AP ART (Including Author, Title, Date, Pertinent Pages, Etc.) AQ Future Fab International, "XPS Analysis on Fluorine Removal by Plasma Cleaning," (Undated) pages 289 AR P.M. Clarke et al., "Gas-Phase Interactions Between WF6 and Metal Surfaces," (1994) Conference Proceedings ULSI-IX - Materials Research Society, pages 411 - 417; 59 68 Y. Shirai et al., "Fluorine Passivation of Metal Surface," (1996) CleanRooms "'96 West Session 602, AS pages 68 - 71 Date Considered \*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through

citation if not in conformance and not considered. Include copy of this form with your communication to applicant.

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M	AR	D.W. Greve et al. Technol. B14(1),	, "Process Cont pages 489 – 491	rol Based On Quadrup 3	oole Mass Spectr	ometry," (1996)	) J. Vac. Sci.				
AL	AS	Los Alamos Natio	onal Laboratory	, "Excimer Laser Cher	mical Problems,	" (1985) U.S. D	ept. of Comm	erce,			
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